SARDAR PATEL UNIVERSITY

M. Sc. (Physics) IV Semester Examination
Day and Date: Tuesday, 26th March, 2019
Time: 10.00 am to 1.00 pm

Subject: Advanced Solid State Electronic Devices

Paper No: PS04EPHY24

		Paper No: PS04EPHY24 Total Marks: 70	
Q.1	(1)	Multiple Choice Questions. The heavy emitter doping is responsible for the band gap shrinkage which is an important BJT design limitation. This limitation can be overcome by	(8)
	(2)	The optoelectronic integrated circuits (OEIC) can be monontaneously technology.	
	(3) (4)	(a) Si (b) GaAs (c) Ge (d) GeSi amongst the following is a heterojunction FET. (a) JFET (b) MOSFET (c) TEGFET (d) CMOS Ionized impurity scattering can be suppressed drastically in an active channel of	·
	(5) (6)	(a) SiMOX (b) MODFET (c) MOSFET (d) Bi-FET detector is the most sensitive photodetector. (a) P-i-N (b) Avalanche (c) P-N diode The multiplication of carriers takes place in diode. (a) p-n junction (b) P-i-N junction (c) avalanche (d) Schottky junction	
	(7)	Positive voltage is applied to in CMOS. (a) source of P-MOSFET, (b) drain of P-MOSFET, (c) source of N-MOSFET, (d) drain of N-MOSFET in inversion mode.	
	(8)	(a) C_m (b) C_s (c) C_{ox} (d) combination of $a_{ox} = a_{ox} = a_{$	(14)
Q.2	(1)	eat at a heard such devices	(-)
	(2) (3) (4) (5)	Why the depletion width in channel is non-uniform in TET: How the impurity scattering is avoided in heterojunction FETs? How the impurity scattering is avoided in heterojunction FETs?	
•	(6)	Draw the schematic structure of MOS capacitor. Write do not require equivalent capacitance of MOS structure. Why the capacitance of metal is neglected in it?	
	(7)	Give a difference between the operation and 1-v characteristies of passes solar cell.	
	(9	Compare the operation of photodecoers and re-	(0)

Q.3	(a)	What are BJT design limitations? How are they addressed by HBT structure? Compare the band diagram of BJT and HBT and show differences and similarities in	(6)
	(b)	their structures. How MESFETs are different from JFETs? Discuss the I-V characteristics of MESFET in active and saturation regimes.	(6)
		OR	40
	(b)	Discuss following effects in detail in case of FETs;	(6)
	(n)	(i) velocity – field relations and	
		(ii) shannal length modulation	(6)
Q.4	(a)	Explain the concept of MODFET constructed using AlGaAs. Also discuss its key	(6)
Ų. 7	(4)		(6)
	(b)	Derive the expression for sheet charge density of electrons in terms of gate voltage on the basis of charge control model of MODFET.	(6)
		OR .	(6)
	(b)	Sketch the equivalent circuit and a cross-sectional diagram of MESFET and derive the	(6)
	(~)	for f_(max) in terms of n-type channel parameters.	(6)
Q.5	(a)	the mades in which the MOS canacitor can be operated. Discuss the	(0)
C		operation of MOS capacitor in all three modes. Draw and explain the density variation	
		c. t. t. t. and holog in MOS capacitor constructed IISING D-DL	(6)
	(b)	Using the circuit diagram, explain in detail the operation of CMOS. Flove that it is used as an inverter. Why the current flowing through CMOS structure is always low?	(0)
		Draw the structure of CMOS. OR	
		OR STATE AND connection at low and high frequencies. Also	(6)
	(b)	Describe the C-V characteristics of MOS capacitor at low and high frequencies. Also	` '
		write the equation of equivalent capacitance of MOS structure in all the three modes. Draw the configuration of avalanche photodiode. Discuss its operation in detail. Why	(6)
Q.6	(a)	Draw the configuration of avalanche photodrode. Discuss its operations	
		does it require heat sink? Mention its advantages and limitations.	(6)
	. (b)	Compare p-n junction photodetector and p-i-n photodetector. OR	
			(6)
	(b)	bandgap material in case of LED? Draw and explain the structure and characteristics	
		bandgap material in case of BBB. Brain and organization of surface are itting IED	
		of surface emitting LED.	

		(2)	